



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Koichiro TANAKA

Serial No. 09/774,637

Filed: February 1, 2001

For: BEAM HOMOGENIZER LASER

IRRADIATION APPARATUS,

SEMICONDUCTOR DEVICE,

AND METHOD OF FABRICATING)

THE SEMICONDUCTOR DEVICE )

)

) Group Art Unit: 2815

) Examiner: J. Diaz

)

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with The United States Postal Service with sufficient postage as First Class Mail in an envelope addressed to: Commissioner for Patents, Washington, D.C. 20231, on 9/30/02

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AMENDMENT AND RESPONSE TO ELECTION REQUIREMENT

Honorable Commissioner for Patents

Washington, D.C. 20231

Sir:

In response to the Office Action of August 29, 2002, please amend the subject application as follows:

IN THE CLAIMS:

Cancel claims 15-41 without prejudice to Applicant's right to file a divisional application with respect thereto.

Please amend claims 1-8 and 11-12 as follows:

1. (Amended) A beam homogenizer for forming a laser beam elongated in one direction on an irradiated surface, comprising:

two reflectors for splitting said laser beam.

2. (Amended) A beam homogenizer of claim 1, wherein said laser beam has a length of 600 mm or more along said one direction on said irradiated surface.

*BT*  
*P1*